IN THE CLAIMS

Please amend Claims 1, 5, 6, 9-13, 17, 18 and 21-24, to read as follows.

1. (Currently Amended) A ferroelectric thin film element comprising a substrate and an epitaxial ferroelectric thin film that has a plurality of crystal faces and that is provided on said substrate,

wherein said epitaxial ferroelectric thin film satisfies a relation $z/z_0 > 1.003$, wherein a crystal face parallel to a crystal face of a surface of said substrate, among the erystal faces of said epitaxial ferroelectric thin film, is taken as a Z crystal face, a face spacing of the Z crystal face is taken as z and a face spacing of the Z crystal face of a material constituting said epitaxial ferroelectric thin film in a bulk state is taken as z_0 where z is the c-axis lattice constant of the epitaxial ferroelectric thin film and z_0 is the c-axis lattice constant of a material constituting said epitaxial ferroelectric thin film in a bulk state, and

wherein said epitaxial ferroelectric thin film also satisfies a relation $0.997 \le x/x_0 \le 1.003$, wherein one of the crystal faces of said epitaxial ferroelectric thin film perpendicular to the Z crystal face is taken as an X crystal face, a face spacing of the X crystal face is taken as x and a face spacing of the X crystal face of the material constituting said epitaxial ferroelectric thin film in a bulk state is taken as x_0 where x is the a-axis lattice constant of the epitaxial ferroelectric thin film and x_0 is the a-axis lattice constant of a material constituting said epitaxial ferroelectric thin film in a bulk state.

2. (Original) A ferroelectric thin film element according to claim 1,

wherein said epitaxial ferroelectric thin film has a thickness within a range of 2 to 100 nm.

- (Original) A ferroelectric thin film element according to claim 1, further comprising at least a buffer layer between said substrate and said epitaxial ferroelectric thin film.
- 4. (Original) A ferroelectric thin film element according to claim 3, wherein at least one of said substrate and said buffer layer is electroconductive.
- 5. (Currently Amended) A ferroelectric thin film element according to claim 1, wherein a crystal orientation degree of the Z a crystal [[face]] plane of said epitaxial ferroelectric thin film parallel to a crystal plane of a surface of said substrate, measured by a $2\theta/\theta$ method with an X-ray incident angle θ to the [[Z]] crystal [[face]] plane of said epitaxial ferroelectric thin film parallel to the crystal plane of the surface of said substrate, is 90 % or higher.
- 6. (Currently Amended) A ferroelectric thin film element according to claim 1, wherein the Z a crystal face plane of said epitaxial ferroelectric thin film parallel to a crystal plane of a surface of said substrate has a crystal orientation degree of 99 % or higher.
- 7. (Original) A ferroelectric thin film element according to claim 1, wherein said epitaxial ferroelectric thin film has a perovskite structure.

- 8. (Original) A ferroelectric thin film element according to claim 1, wherein said epitaxial ferroelectric thin film includes a lead (Pb) atom or an oxygen (O) atom as a constituent atom.
- 9. (Currently Amended) A ferroelectric thin film element according to claim 1, wherein said epitaxial ferroelectric thin film has a tetragonal crystal structure and the Z a crystal face plane of said epitaxial ferroelectric thin film parallel to a crystal plane of a surface of said substrate is a (001) face plane.
- 10. (Currently Amended) A ferroelectric thin film element according to claim 1, wherein said epitaxial ferroelectric thin film has a rhombohedral crystal structure and the Z a crystal face plane of said epitaxial ferroelectric thin film parallel to a crystal plane of a surface of said substrate is a (111) face plane.
- 11. (Currently Amended) A ferroelectric thin film element according to claim 1, wherein said epitaxial ferroelectric thin film has a hexagonal crystal structure and the Z a crystal face plane of said epitaxial ferroelectric thin film parallel to a crystal plane of a surface of said substrate is a (0001) face plane.
- 12. (Currently Amended) A ferroelectric thin film element according to claim 1, wherein said epitaxial ferroelectric thin film has a rhombic crystal structure and

the Z a crystal face plane of said epitaxial ferroelectric thin film parallel to a crystal plane of a surface of said substrate is a (011) face plane.

13. (Currently Amended) A piezoelectric actuator comprising a substrate and an epitaxial ferroelectric film that has a plurality of crystal faces and that is provided on said substrate,

wherein said epitaxial ferroelectric film satisfies a relation $z/z_0 > 1.003$, wherein a crystal face parallel to a crystal face of a surface of said substrate, among the crystal faces of said epitaxial ferroelectric film, is taken as a Z crystal face, a face spacing of the Z crystal face is taken as z and a face spacing of the Z crystal face of a material constituting said epitaxial ferroelectric film in a bulk state is taken as z_0 where z is the c-axis lattice constant of the epitaxial ferroelectric film and z_0 is the c-axis lattice constant of a material constituting said epitaxial ferroelectric film in a bulk state, and

wherein said epitaxial ferroelectric film also satisfies a relation $0.997 \le x/x_0 \le 1.003$, wherein one of the crystal faces of said epitaxial ferroelectric film perpendicular to the Z crystal face is taken as an X crystal face, a face spacing of the X crystal face is taken as x and a face spacing of the X crystal face of the material constituting said epitaxial ferroelectric film in a bulk state is taken as x_0 where x is the a-axis lattice constant of the epitaxial ferroelectric film and x_0 is the a-axis lattice constant of a material constituting said epitaxial ferroelectric film in a bulk state.

- 14. (Previously Presented) A piezoelectric actuator according to claim 13, wherein said epitaxial ferroelectric film has a thickness within a range of 100 nm to 10 μ m.
- 15. (Original) A piezoelectric actuator according to claim 13, further comprising at least a buffer layer between said substrate and said epitaxial ferroelectric film.
- 16. (Original) A piezoelectric actuator according to claim 15, wherein at least one of said substrate and said buffer layer is electroconductive.
- 17. (Currently Amended) A piezoelectric actuator according to claim 13, wherein a crystal orientation degree of the Z a crystal face plane of said epitaxial ferroelectric film parallel to a crystal plane of a surface of said substrate, measured by a $2\theta/\theta$ method with an X-ray incident angle θ to the [[Z]] crystal face plane of said epitaxial ferroelectric film parallel to the crystal plane of the surface of said substrate, is 90 % or higher.
- 18. (Currently Amended) A piezoelectric actuator according to claim

 13, wherein the Z a crystal face plane of said epitaxial ferroelectric film parallel to a crystal plane of a surface of said substrate has a crystal orientation degree of 99 % or higher.

- 19. (Original) A piezoelectric actuator according to claim 13, wherein said epitaxial ferroelectric film has a perovskite structure.
- 20. (Original) A piezoelectric actuator according to claim 13, wherein said epitaxial ferroelectric film includes a lead (Pb) atom or an oxygen (O) atom as a constituent atom.
- 21. (Currently Amended) A piezoelectric actuator according to claim 13, wherein said epitaxial ferroelectric film has a tetragonal crystal structure and the Z a crystal face plane of said epitaxial ferroelectric film parallel to a crystal plane of a surface of said substrate is a (001) face plane.
- 22. (Currently Amended) A piezoelectric actuator according to claim 13, wherein said epitaxial ferroelectric film has a rhombohedral crystal structure and the Z a crystal face plane of said epitaxial ferroelectric film parallel to a crystal plane of a surface of said substrate is a (111) face plane.
- 23. (Currently Amended) A piezoelectric actuator according to claim 13, wherein said epitaxial ferroelectric film has a hexagonal crystal structure and the Z a crystal face plane of said epitaxial ferroelectric film parallel to a crystal plane of a surface of said substrate is a (0001) face plane.

- 24. (Currently Amended) A piezoelectric actuator according to claim 13, wherein said epitaxial ferroelectric film has a rhombic crystal structure and the Z a crystal face plane of said epitaxial ferroelectric film parallel to a crystal plane of a surface of said substrate is a (011) face plane.
- 25. (Original) A liquid discharge head for discharging a liquid utilizing a piezoelectric actuator according to claim 13.